

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Previously Presented) A method for polishing a glass hard disk platter, comprising polishing a glass hard disk platter using a stable slurry in which cerium(IV) oxide particles having an average secondary particle size of 0.1 to 0.5 μm are dispersed in water, which contains CeO_2 in a concentration of 0.2 to 30 wt%, and contains a quaternary ammonium ion (NR_4^+ , where R is an organic group) in a $(\text{NR}_4^+)/(\text{CeO}_2)$ molar ratio in a range of 0.001 to 1, wherein a proportion of cerium expressed as a ratio of (cerium oxide)/(cerium oxide + other rare earth oxides) in the cerium(IV) oxide particles is 95% or more based on weight, and the stable slurry is a slurry of surface-modified cerium(IV) oxide obtained by heat-treating cerium(IV) oxide that is obtained by blowing oxygen or a gas containing oxygen into a suspension obtained by reacting a cerium (III) salt with an alkaline substance in a $(\text{OH})/(\text{Ce}^{3+})$ molar ratio of 3 to 30, in an aqueous medium in the presence of an ammonium salt having a non-oxidative anionic component selected from the group consisting of ammonium carbonate, ammonium hydrogen carbonate, and mixtures thereof, and the stable slurry has a pH from 5 to 6.
2. (Canceled)
3. (Original) The method according to claim 1, wherein a specific surface area of the cerium(IV) oxide particles is 2 to 200 m^2/g .
4. (Canceled)
5. (Previously Presented) The method according to claim 1, wherein the cerium (III) salt and the alkaline substance are reacted under an inert gas atmosphere.
6. (Previously Presented) The method according to claim 1, wherein the cerium (III) salt and the alkaline substance are reacted at an atmospheric pressure.

7. (Canceled)